

PTO/SR/21 (09-04)

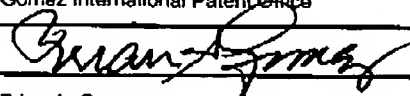
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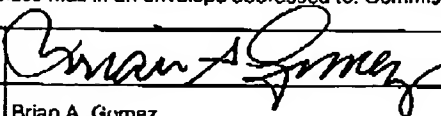
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TRANSMITTAL FORM (to be used for all correspondence after initial filing)	Application Number	10/526,383	
	Filing Date	13 September 2005	
	First Named Inventor	Sakai	
	An Unit	1752	
	Examiner Name	Shi J. Lee	
Total Number of Pages in This Submission	3	Attorney Docket Number	Toyo-3

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ENCLOSURES (Check all that apply)		
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Remarks Request is being faxed to 571-273-8300		

SIGNATURE OF APPLICANT, ATTORNEY, OR AGENT		
Firm Name	Gomez International Patent Office	
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Printed name	Brian A. Gomez	
Date	01 June 2006	Reg. No. 44,718

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**PATENT APPLICATION
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

IN THE APPLICATION OF
Nobuji Sakai, et al.

DOCKET NO.: Toyo-3

SERIAL NO.: 10/526,383

EXAMINER: Sin J. Lee

FILED: September 13, 2005

ART UNIT: 1752

CONFIRMATION NO.: 3829

**TITLE: Radiation-Sensitive Negative-Type Resist Composition for Pattern
Formation and Pattern Formation Method**

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REQUEST FOR CORRECTED FILING RECEIPT AND REPUBLICATION

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Sir:

The Applicants request that the Filing Receipt in the above-identified application be corrected as follows:

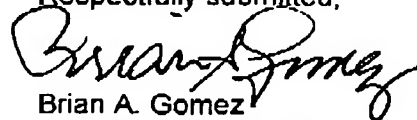
From: Foreign Applications
Japan 200-252926 08/30/2002

To: Foreign Applications
Japan 2002-252926 08/30/2002

A copy of the corresponding PCT publication is attached as evidence.

Applicant requests that the correction be effected prior to the projected publication date of 03 August 2006.

Respectfully submitted,



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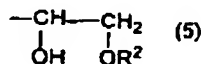
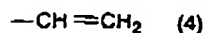
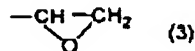
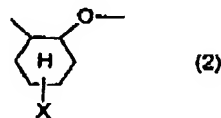
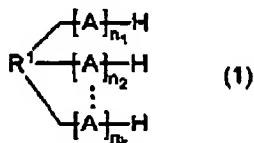
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[Continued on next page]

(54) Title: RADIATION-SENSITIVE NEGATIVE-TYPE RESIST COMPOSITION FOR PATTERN FORMATION AND PATTERN FORMATION METHOD



(57) Abstract: The radiation sensitive negative-type resist composition for pattern formation containing an epoxy resin, a radiation-sensitive cationic polymerization initiator, and a solvent for dissolving the epoxy resin therein, characterized in that the resist composition, through drying, forms a resist film having a softening point falling within a range of 30 to 120 °C and that the epoxy resin is represented by formula (1): (wherein R1 represents a moiety derived from an organic compound having k active hydrogen atoms (k represents an integer of 1 to 100); each of n₁, n₂, through n_k represents 0 or an integer of 1 to 100; the sum of n₁, n₂, through n_k falls within a range of 1 to 100; and each of "A"s, which may be identical to or different from each other, represents an oxycyclohexane skeleton represented by formula (2): (wherein X represents any of groups represented by formulas (3) to (5): and at least two groups represented by formula (3) are contained in one molecule of the epoxy resin)).

WO 2004/023213 A1